L Number	Hits	Search Text	DB	Time stamp
1	5191	(250/492.22,492.2,492.3).CCLS.	USPAT; US-PGPUB; EPO; JPO;	2004/04/04 14:19
2	20407	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:20
3	511	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:49
4	425	(charged adj particle))near beam) and deflect\$4 and control\$4 near4 signal near4 stor\$4)) and control	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:22
5	425	(charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:22
6	35	near1 signal) (((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:27
8	2	storing) nearl (control near signal))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
7	10	<pre>((plurality or multiple) near4 beam) ((((((electron or charged-particle or   (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal)))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:25
9	3	and (shift near register\$4) ((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
10	35		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04
11	14	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04
12	1	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:32

	6071		TIGDEM .	1 2004 /04 /04
13	6071	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:33
i e	1		IBM_TDB	
14	3551	<pre>(((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:34
15	973	((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/04/04 14:34
16	345	substrate or sample)) and (deflect\$5 near2 control\$4) (((((electron or charged-particle or	DERWENT; IBM_TDB USPAT;	2004/04/04
		<pre>(charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)</pre>	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	14:40
18	2	<pre>(((((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:36
17	3	storage)) and (stor\$4 near5 deflect\$4) (((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
19	703	<pre>signal)) and (control\$4 near signal near storage) ((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:40
20	5	(charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)) and (control\$4 near signal)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
21	17	storage) Hashimoto near Shin-Ichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:41
22	6121	<pre>(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:50
23	103	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:51
24	37	<pre>(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:51

25	16	(((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle))near beam) and	US-PGPUB;	14:52
		deflect\$4 and control\$4) and (control\$4	EPO; JPO;	
		near2 signal)) and (stor\$4 near ((control	DERWENT;	
		or deflect\$4) near2 (output or signal))))	IBM TDB	
		and (deflect\$5 near control\$4)) and	_	
		(substrate or wafer or semiconductor)		
26	10	((((((electron or charged-particle or	USPAT;	2004/04/04
	l \	(charged adj particle))near beam) and	US-PGPUB;	14:52
1		deflect\$4 and control\$4) and (control\$4	EPO; JPO;	}
		near2 signal)) and (stor\$4 near ((control	DERWENT;	
		or deflect\$4) near2 (output or signal))))	IBM TDB	
		and (deflect\$5 near control\$4)) and		
		(substrate or wafer or semiconductor))		
		and (electrode or deflector)		

L	Hits	Search Text	DB	Time stamp
Number				0004/04/04
1	5191	(250/492.22,492.2,492.3).CCLS.	USPAT; US-PGPUB;	2004/04/04 14:19
2	20407	((electron or charged-particle or	EPO; JPO; DERWENT; IBM_TDB USPAT;	2004/04/04
		(charged adj particle))near beam) and deflect\$4 and control\$4	US-PGPUB; EPO; JPO; DERWENT; IBM TDB	16:49
3	511	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:49
4	425	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and control near1 signal</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:22
5	425	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
6	35	<pre>(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
8	2	<pre>(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and (shift near register\$4)) and ((plurality or multiple) near4 beam)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:24
7	10		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
9	3	((((((electron or charged-particle or (charged adj particle)) near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
10	35	(charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
11	14	(charged adj particle)) near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
12	1	(((((electron or charged-particle or (charged adj particle)) near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04

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13	6071	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:33
14	3551	(((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/04/04 14:34
15	973	substrate or sample)  ((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/04/04 14:34
16	345	substrate or sample)) and (deflect\$5 near2 control\$4) (((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/04/04 14:40
18	2	<pre>substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal) ((((((electron or charged-particle or (charged adj particle)) near (beam or</pre>	DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/04/04 14:36
		expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near storage)) and (stor\$4 near5 deflect\$4)	EPO; JPO; DERWENT; IBM_TDB	
17	3	<pre>((((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
19	703	<pre>signal)) and (control\$4 near signal near storage) ((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/04 14:40
20	5	signal) (((((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)) and (control\$4 near signal near	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:41
21	17	storage) Hashimoto near Shin-Ichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:41
22	6121	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:50
23	103	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 16:59
24	37	T	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:51

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25	16	<pre>((((((electron or charged-particle or   (charged adj particle))near beam) and   deflect\$4 and control\$4) and (control\$4   near2 signal)) and (stor\$4 near ((control   or deflect\$4) near2 (output or signal))))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/04 14:52
		and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)	15.1_155	į.
26	10	<pre>(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
27	7	and (electrode or deflector) (((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)) and (electrode or deflector)) and register	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:45
28	150	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:50
29	46	<pre>((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
30	18	((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
31	13	<pre>(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
32	6	<pre>(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and switch\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04
34	1	<pre>(((((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and switch\$4) and binary ) and analog</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04

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33	3	(((((((electron or charged-particle or (charged adj particle))near beam) and	USPAT; US-PGPUB;	2004/04/04 16:52
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or	IBM_TDB	
		two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or		
		sample or semiconductor)) and switch\$4)		
		and binary		
35	5	((((((electron or charged-particle or	USPAT;	2004/04/04
	_	(charged adj particle))near beam) and	US-PGPUB;	17:01
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or	IBM_TDB	
		two) near4 (beam or beamlet))) and	_	•
		expos\$4) and (wafer or substrate or		
		sample or semiconductor)) and (clock or		
	_	timer or timing)		
36	2	((((((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle)) near beam) and	US-PGPUB;	16:57
		deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or	EPO; JPO; DERWENT;	
		output))) and ((plurality or multiple or	IBM TDB	1
		two) near4 (beam or beamlet))) and	1511_155	
		expos\$4) and (wafer or substrate or		1
		sample or semiconductor)) and (clock or		]
		timer or timing)) and (shift near		!
		register)		
37	1	((((((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle)) near beam) and	US-PGPUB;	16:55
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and	IBM_TDB	
		expos\$4) and (wafer or substrate or		!
	1	sample or semiconductor)) and (clock or		
		timer or timing)) and (shift near		
		register)) and (flipflop\$4 or (flip adj		
		flop) or flip-flop\$4)		
38	1	( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( (	USPAT;	2004/04/04
		(charged adj particle))near beam) and	US-PGPUB;	16:58
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and	IBM_TDB	
		expos\$4) and (wafer or substrate or		
		sample or semiconductor)) and (clock or		
		timer or timing)) and (flipflop\$4 or		
		(flip adj flop) or flip-flop\$4)		
39	3		USPAT;	2004/04/04
		(charged adj particle))near beam) and	US-PGPUB;	16:56
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or	IBM_TDB	
İ		two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or	1	
		sample or semiconductor)) and (shift near		
		register)		
40	1	l	USPAT;	2004/04/04
-		(charged adj particle)) near beam) and	US-PGPUB;	16:56
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	,
		near4 deflect\$4 near4 (signal or	DERWENT;	
l		output))) and ((plurality or multiple or	IBM_TDB	
l		two) near4 (beam or beamlet))) and		
İ		expos\$4) and (wafer or substrate or		
		sample or semiconductor)) and (shift near register)) and (flipflop\$4 or (flip adj		
		flop) or flip-flop\$4)		
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				0004/04/04
41	1	((((((electron or charged-particle or	USPAT;	2004/04/04
1		(charged adj particle)) near beam) and	US-PGPUB;	16:57
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and ((plurality or multiple or	IBM_TDB	
		two) near4 (beam or beamlet))) and		
		expos\$4) and (wafer or substrate or		
		sample or semiconductor)) and (flipflop\$4		
		or (flip adj flop) or flip-flop\$4)		
42	28	((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle))near beam) and	US-PGPUB;	16:57
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and (flipflop\$4 or (flip adj	IBM_TDB	
	ļ	flop) or flip-flop\$4)		
43	7	(((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle))near beam) and	US-PGPUB;	16:59
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
		near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and (flipflop\$4 or (flip adj	IBM TDB	
		flop) or flip-flop\$4)) and ((plurality or	_	
		multiple or two) near4 (beam or beamlet))		
44	3	(((((electron or charged-particle or	USPAT;	2004/04/04
		(charged adj particle)) near beam) and	US-PGPUB;	16:58
		deflect\$4 and control\$4) and (stor\$4	EPO; JPO;	
	Į	near4 deflect\$4 near4 (signal or	DERWENT;	
		output))) and (flipflop\$4 or (flip adj	IBM TDB	
		flop) or flip-flop\$4)) and ((plurality or	_	
		multiple or two) near4 (beam or		
		beamlet))) and (shift near register)		1
45	68	((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
		(shift near register)	US-PGPUB;	16:58
		( <del></del> ,	EPO; JPO;	
			DERWENT;	
			IBM TDB	<b> </b>
46	13	(((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
10	10	(shift near register)) and (flipflop\$4 or	US-PGPUB;	16:58
		(flip adj flop) or flip-flop\$4)	EPO; JPO;	
[		(lilp day liop) of lilp liop419	DERWENT;	
i			IBM TDB	
48	1	(((((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
"		(shift near register)) and (flipflop\$4 or	US-PGPUB;	17:25
1		(flip adj flop) or flip-flop\$4)) and	EPO; JPO;	17.20
<b>!</b>		((plurality or multiple or two) near4	DERWENT;	
		(beam or beamlet))) and (stor\$4 near	IBM TDB	
		((control or deflect\$4) near2 (output or	10.1_100	
		signal)))		
47	7	((((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
* '	∣ ′ I	(shift near register)) and (flipflop\$4 or	US-PGPUB;	17:00
		(flip adj flop) or flip-flop\$4)) and	EPO; JPO;	17.00
		((plurality or multiple or two) near4	DERWENT;	
		((pidrality of multiple of two, heary (beam or beamlet))	IBM TDB	
49	5	(((((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
47	5	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or	US-PGPUB;	17:00
				17.00
		(flip adj flop) or flip-flop\$4)) and	EPO; JPO;	
j		((plurality or multiple or two) near4	DERWENT;	
_	ا ہا	(beam or beamlet))) and deflect\$4	IBM_TDB	2004/04/04
50	5	((((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or	USPAT;	17:00
1			US-PGPUB;	17:00
	l	(flip adj flop) or flip-flop\$4)) and	EPO; JPO;	
		((plurality or multiple or two) near4	DERWENT;	
j		(beam or beamlet))) and deflect\$4) and	IBM_TDB	
_	<u> </u>	stor\$4	110 D 2 T	2004/04/04
51	5	(((((((250/492.22,492.2,492.3).CCLS.) and	USPAT;	2004/04/04
		(shift near register)) and (flipflop\$4 or	US-PGPUB;	17:01
1		(flip adj flop) or flip-flop\$4)) and	EPO; JPO;	
1		(/niurality or multiple or two) pears	DERWENT;	i
		((plurality or multiple or two) near4		
		(beam or beamlet))) and deflect\$4) and stor\$4) and (clock or timer or timing)	IBM_TDB	

52 2 ((((((((250/492.22,492.3).CCLS.) USPAT; and (shift near register)) and US-PGPUB; (flipflop\$4 or (flip adj flop) or EPO; JPO;	2004/04/04 17:02
	11.02
flip-flop\$4)) and ((plurality or multiple   DERWENT;	
or two) near4 (beam or beamlet))) and IBM TDB	
deflect\$4) and stor\$4) and (clock or	
timer or timing)) and (stor\$4 near5	
deflect\$4)	2004/04/04
53 3 (((((((((250/492.22,492.2,492.3).CCLS.) USPAT;	
and (shift near register)) and US-PGPUB;	17:02
(flipflop\$4 or (flip adj flop) or EPO; JPO;	
flip-flop\$4)) and ((plurality or multiple   DERWENT;	
or two) near4 (beam or beamlet))) and IBM_TDB	
deflect\$4) and stor\$4) and (clock or	
timer or timing)) and (stor\$4 near5	
(signal or output))	0004/04/04
54 86 ((((electron or charged-particle or USPAT;	2004/04/04
(charged adj particle))near beam) and US-PGPUB;	17:26
deflect\$4 and control\$4) and (control\$4 EPO; JPO;	
near4 signal near4 stor\$4)) and (stor\$4 DERWENT;	
near4 (deflect\$4))   IBM_TDB	
55   42   ((((electron or charged-particle or USPAT;	2004/04/04
(charged adj particle))near beam) and US-PGPUB;	17:26
deflect\$4 and control\$4) and (control\$4   EPO; JPO;	
near4 signal near4 stor\$4)) and (stor\$4   DERWENT;	
near4 (deflect\$4))) and binary   IBM_TDB	
56   34   (((((electron or charged-particle or USPAT;	2004/04/04
(charged adj particle))near beam) and US-PGPUB;	17:26
deflect\$4 and control\$4) and (control\$4   EPO; JPO;	
near4 signal near4 stor\$4)) and (stor\$4   DERWENT;	
near4 (deflect\$4))) and binary) and IBM_TDB	
analog	
58 1 (((((((electron or charged-particle or USPAT;	2004/04/04
(charged adj particle))near beam) and   US-PGPUB;	17:27
deflect\$4 and control\$4) and (control\$4   EPO; JPO;	
near4 signal near4 stor\$4)) and (stor\$4   DERWENT;	
near4 (deflect\$4))) and binary) and IBM TDB	
analog) and (identif\$4 with deflect\$4))	
and ((diagnos\$4 or analyz\$4) with	
deflector)	
3 ((((((electron or charged-particle or USPAT;	2004/04/04
(charged adj particle))near beam) and US-PGPUB;	17:28
deflect\$4 and control\$4) and (control\$4 EPO; JPO;	
near4 signal near4 stor\$4)) and (stor\$4 DERWENT;	
near4 (deflect\$4))) and binary) and IBM_TDB	
analog) and (identif\$4 with deflect\$4)	